

Applicant(s): Alexander Tregub et al.

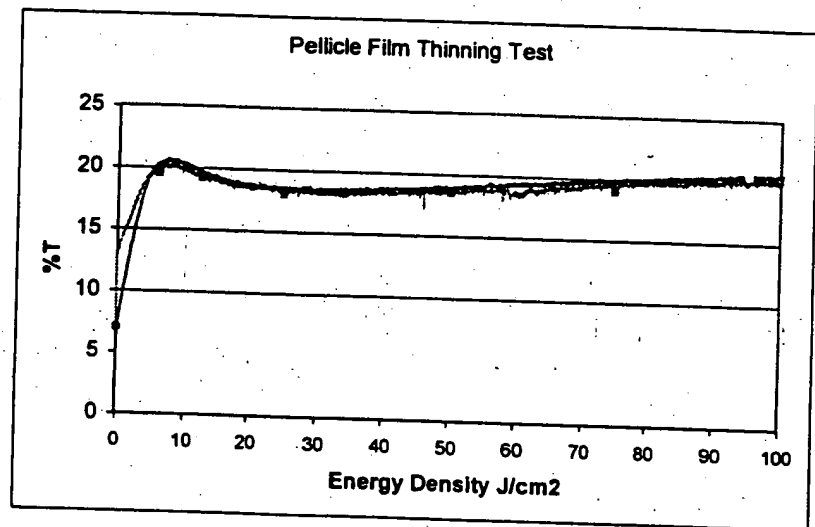
PROCESS TO OPTIMIZE PROPERTIES OF POLYMER
PELLICLES AND RESIST FOR LITHOGRAPHY
APPLICATIONS

Fig.1

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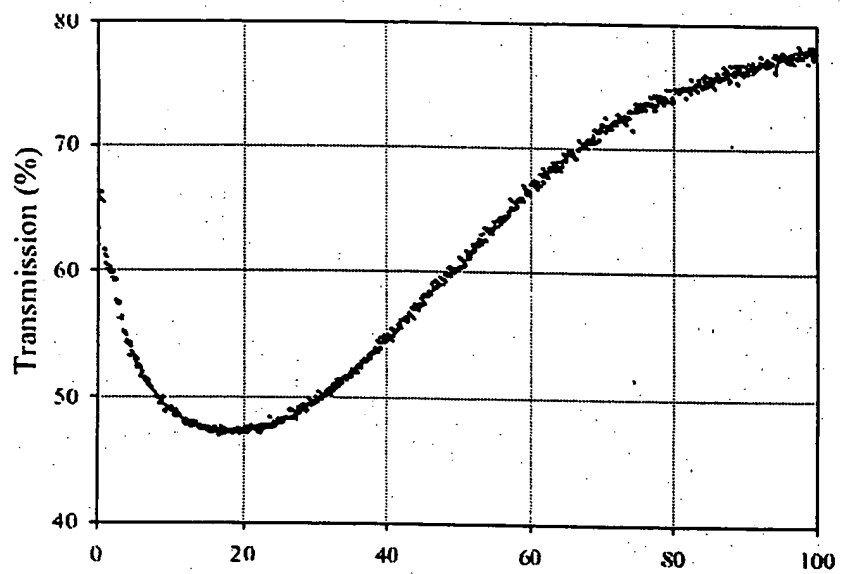
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Fig. 2

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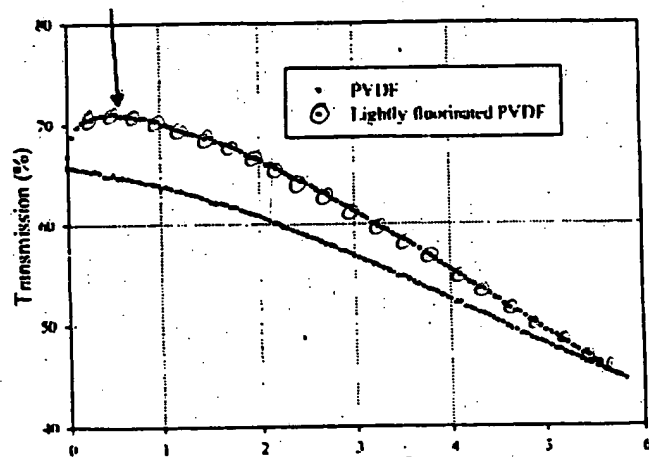


Fig 3

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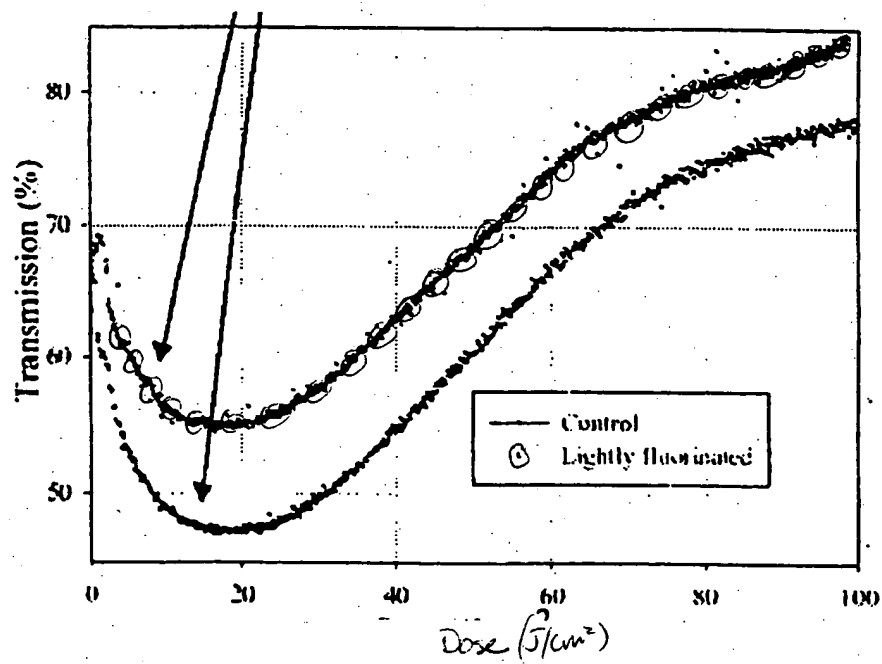


FIG. 4

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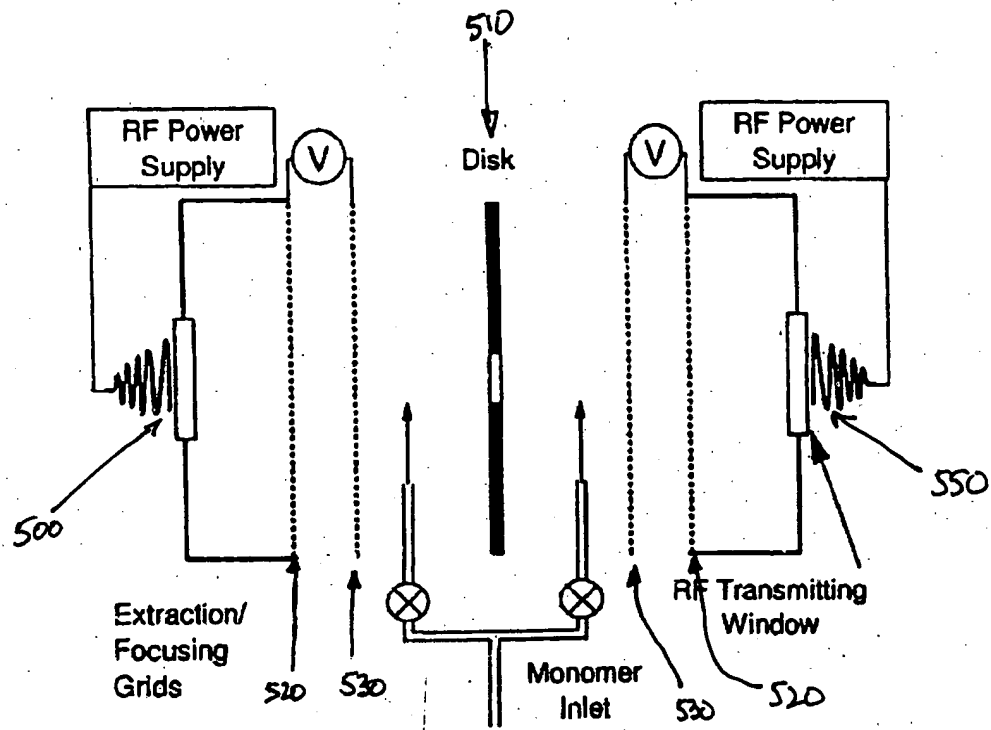
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FIG. 5

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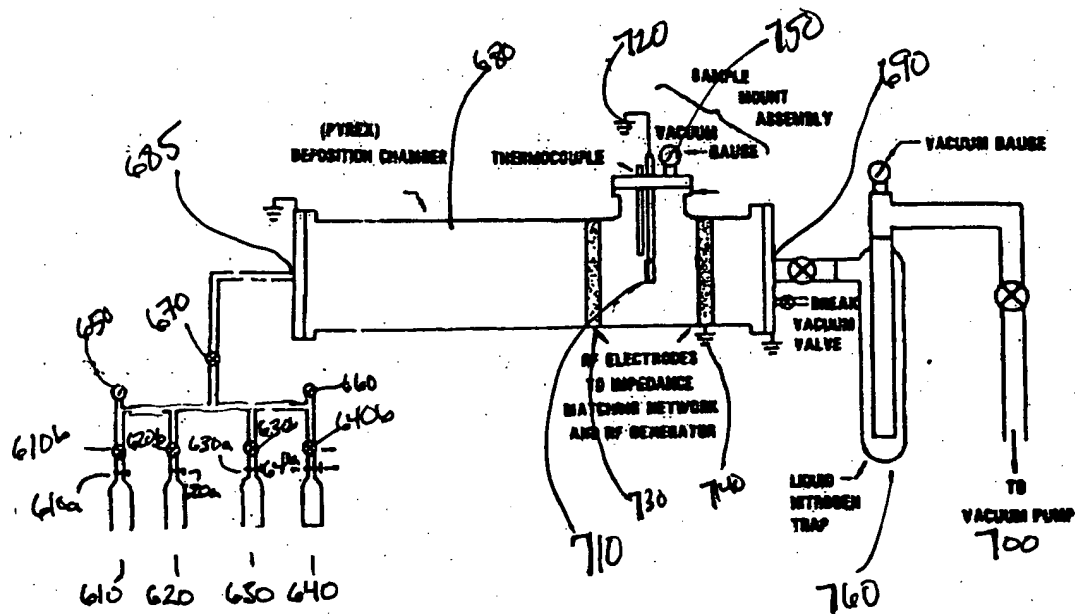
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FIG. 6

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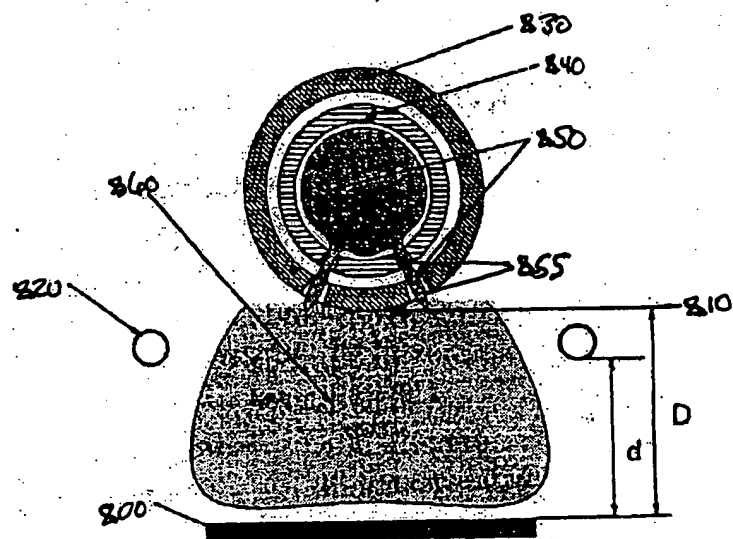
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FIG. 7

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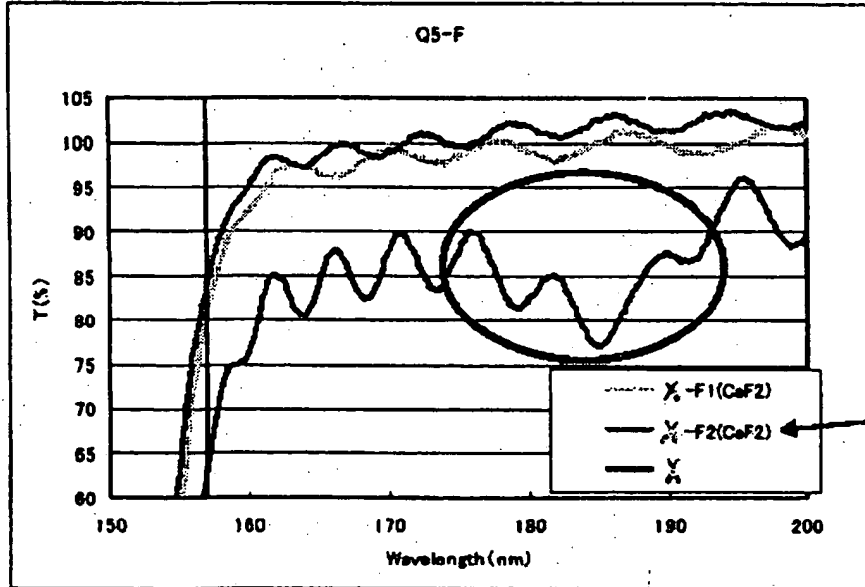
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FIG. 8

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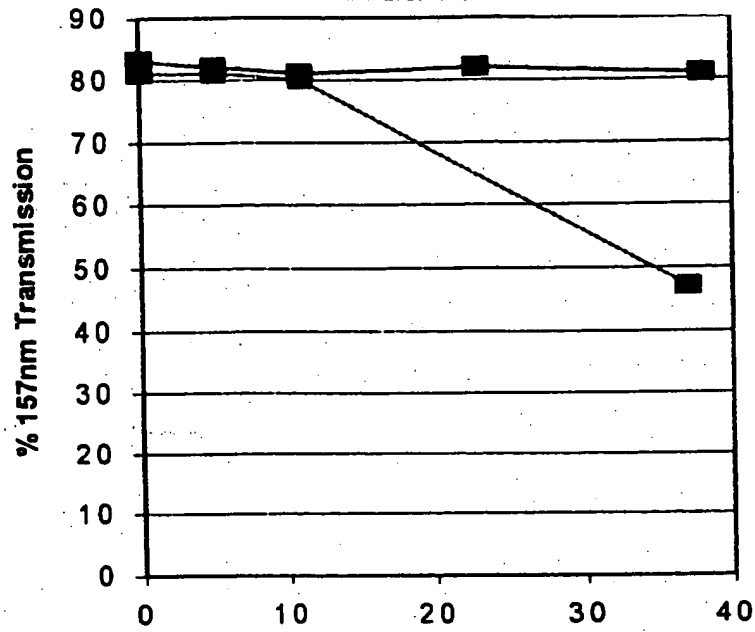
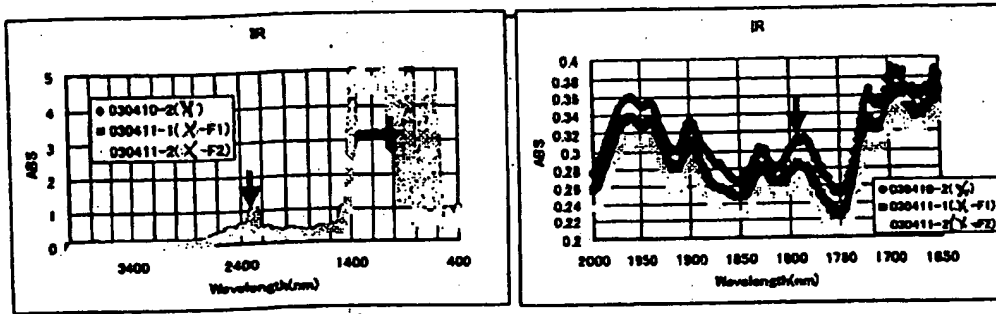
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Fig. 9

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Peak intensity ratio(1790cm-1 vs 2290cm-1)

	X	X-F1	X-F2
Peak intensity ratio	0.488		0.409

FIG. 10